

TECHNICAL PUBLICATIONS

DR MATTHEW F. LAMBRINOS

M. F. Lambrinos, R. Valizadeh, and J. S. Colligon, *Effects of bombardment on optical properties during the deposition of silicon nitride by reactive ion beam sputtering*, Applied Optics, 35 (19), (1996), 3620-26.

M. F. Lambrinos, R. Valizadeh, and J. S. Colligon, *Synthesis of silicon oxynitride by ion beam sputtering and the effects of ion-assisted bombardment*, Nuclear Instruments and Methods in Physics Research, b. 127-128, (1997) 369.

M. F. Lambrinos, M. P. Besland, A. Gagnaire, P. Louis, S. Callard and J. Joseph, *In-situ photoluminescence control during fabrication of SiO₂/InP structure*, Journal of the Electrochemical Society 144 (6), (1997) 2086-95.

M. F. Lambrinos, R. Valizadeh, and J. S. Colligon, *Electrical properties of ion beam sputtered and ion-assisted SiO₂, SiO_xN_y and SiN_x films on silicon*, Journal of Vacuum Science and Technology, January, 1997.

M. F. Lambrinos, R. Valizadeh, and J. S. Colligon, *Synthesis of silicon oxynitride by ion beam sputtering and the effects of nitrogen ion-assisted bombardment*, 10th International Conference on Ion Beam Modification of Materials (IBMM-96), Albuquerque, New Mexico, USA, 1996.

M. P. Besland, S. Jourba, M. Lambrinos, P. Louis, P. Viktorovitch, and G. Hollinger, *Optimized SiO₂/InP structures prepared by electron cyclotron resonance plasma*, Journal of Applied Physics, 80(5), (1996), 3100-9.

J. Joseph, M. P. Besland, S. Callard, A. Gagnaire, M. Lambrinos, and G. Hollinger, *In-situ control during growth of SiO₂ films on InP by ECR plasma*, Proceedings of the Tenth Symposium on Plasma Processing, San Francisco, 1994.